

**AMENDMENTS TO THE CLAIMS**

*Please enter the following amendments:*

1. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of structures of the plasma display panel are formed with photolithography, wherein a position on a photosensitive material corresponding to one of the structures of the plasma display panel is exposed twice using successive first and second exposures, each of the structures extends primarily in a lengthwise direction and has a width  $w$  in a widthwise direction orthogonal to the lengthwise direction, and a photomask and the photosensitive material are moved in the widthwise direction relative to each other by a distance less than  $w$  between the first and second exposures.

2. (Currently Amended) A method of manufacturing a plasma display panel, in which a plurality of electrodes of the plasma display panel are formed with photolithography, wherein a position on a photosensitive material corresponding to one of the electrodes is exposed twice using successive first and second exposures, exposure parts of a photomask for forming the electrodes are disposed periodically with a pitch  $p$ , and a photomask and the photosensitive material are moved relative to each other by two or more integral times the distance  $p$  between the first and second exposures.

3 – 7. (Cancelled)

8. (Previously Presented) The method according to claim 1, wherein the structures are address electrodes formed by exposing a photosensitive silver paste polymerized by exposure to light.

9. (Previously Presented) The method according to claim 2, wherein the electrodes are address electrodes formed by exposing a photosensitive silver paste polymerized by exposure to light.

10 – 12. (Canceled)